

Image

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

2823

Applicant: Fernando Gonzalez et al.

Title: METHOD TO CHEMICALLY REMOVE METAL IMPURITIES FROM POLYCID GATE  
SIDEWALLS

Docket No.: 303.775US1

Filed: August 30, 2001

Examiner: George Fourson

Customer No.: 21186



Serial No.: 09/945553

Due Date: January 9, 2004

Group Art Unit: 2823

Confirmation No.: 1842

**MS Non-Fee Amendment**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

We are transmitting herewith the following attached items (as indicated with an "X"):

☒ A return postcard.

☒ A Response to Restriction Requirement and Preliminary Amendment(13 Pages).

If not provided for in a separate paper filed herewith, Please consider this a **PETITION FOR EXTENSION OF TIME** for sufficient number of months to enter these papers and please charge any additional fees or credit overpayment to Deposit Account No. 19-0743.

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.

Customer Number 21186

By: S. Arora

Atty: Suneel Arora

Reg. No. 42,267

CERTIFICATE UNDER 37 CFR 1.8: The undersigned hereby certifies that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail, in an envelope addressed to: MS Non-Fee Amendment, Commissioner for Patents, P.O.Box 1450, Alexandria, VA 22313-1450, on this 9 day of January, 2004.

Name

Tina Kohut

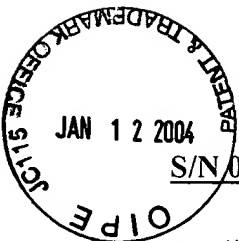
Signature

Z. Ut

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.

(GENERAL)

Customer Number 21186



S/N 09/945553

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Fernando Gonzalez et al.	Examiner:	George Fourson
Serial No.:	09/945553	Group Art Unit:	2823
Filed:	August 30, 2001	Docket:	303.775US1
Title:	METHOD TO CHEMICALLY REMOVE METAL IMPURITIES FROM POLYCIDE GATE SIDEWALLS		

---

**RESPONSE TO RESTRICTION REQUIREMENT  
AND PRELIMINARY AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

In response to the Restriction Requirement mailed December 9, 2003, please amend the application as follows and enter the following remarks. Applicant acknowledges the Examiner's withdrawal of the previous restriction between species one through four.

In response to the present restriction requirement between Species I (polysilicon is oxidized under conditions that reduce redeposition of volatilized metal) and Species II (gate stack is etched under conditions that reduced redeposition of volatilized metal), Applicant elects Species I, without traverse. Applicant agrees with the Examiner's position that claims 9, 11, 14, 17, 18, 19, 21, and 22 are generic to both Species I and II. Applicant further believes that claims 10, 12, 15, and 20 are generic to both Species I and II.

In response to the present restriction requirement between Subspecies I (conditions comprise the presence of a gaseous F containing compound) and Subspecies II (conditions comprise the presence of a solid F containing compound), Applicant elects Subspecies I, without traverse. Applicant believes that claims 1, 2, 7, 9, 10, 11, 14, 17, 18, 19, 20, 21, and 22 are generic to both Subspecies I and Subspecies II.

Please enter the following amendment.